



Docket No.: 50212-211

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Kenichi ARIMURA, et al.

Serial No.: 09/807,902

Group Art Unit: 1763

Filed: April 19, 2001

Examiner: R. Bueker

For: **WAFER SUPPORT IN SEMICONDUCTOR PRODUCTION APPARATUS**

AMENDMENT

Commissioner for Patents
Washington, DC 20231

Sir:

In response to the non-final Office Action dated May 17, 2002, reconsideration is requested in view of the following amendments and remarks.

IN THE CLAIMS

The claims are amended as follows:

- C1
- 5257
1. A semiconductor production apparatus including a process chamber; a wafer support disposed within said process chamber for supporting a semiconductor wafer; and a heating source for heat treatment of the semiconductor wafer supported by said wafer support;
wherein said wafer support comprises a susceptor having an upper surface for mounting said semiconductor wafer thereon, and a susceptor support shaft for supporting said susceptor from thereunder; wherein said susceptor support shaft having a main shaft

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